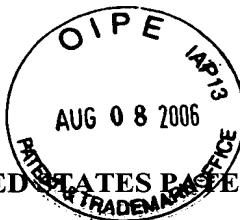


Docket No. 290430US0X PCT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Markus PRIDOEHL, et al.

SERIAL NO: 10/579,762

GAU:

FILED: May 18, 2006

EXAMINER:

FOR: NANOSCALE, CRYSTALLINE SILICON POWDER

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- The applicant(s) wish to make of record the references cited in the International Search Report and listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- Attached is a list of applicant's pending application(s), published application(s) or issued patent(s) which may be related to the present application. In accordance with the waiver of 37 CFR 1.98 dated September 21, 2004, copies of the cited pending applications are not provided. Cited published and/or issued patents, if any, are listed on the attached PTO form 1449.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 290430US0X PCT	SERIAL NO. 10/579,762	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Markus PRIDOEHL, et al.		
				FILING DATE May 18, 2006	GROUP	
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					
	AM					
	AN					
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
	AO	2 591 412	06/12/87	FR(English abstract only)	YES	NO
	AP	01/08795	02/08/01	WO		NO
	AQ	0 214 489	03/18/87	EP		NO
	AR	0 680 384	11/08/95	EP(equivalnet of US 5 334 423)		NO
	AS					
	AT					
	AU					
	AV					
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)						
	AW	LI, Yali et al., "Preparation of Ultrafine Si Powders from SiH ₄ by Laser-induced Gas Phase Reaction" Journal of Materials Science and Technology, Vol. 11, Pages 71-74, 1995.				
	AX	COSTA, J. et al., "Preparation of nanoscale amorphous silicon based powder in a square-wave-modulated rf plasma reactor", Vacuum, Vol. 45, No. 10/11, Pages 1115-1117, 1994.				
	AY	WIGGERS, H. et al., "Silicon Particle Formation by Pyrolysis of Silane in a Hot Wall Gasphase Reactor", Chemical Engineering and Technology, Vol. 24, No.3, Pages 261-264, 2001.				
	AZ				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner					Date Considered	
<p>*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>						